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| APPLICATION NO. | FILING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. |
|---|-------------|----------------------|-----------------------------|------------------|
| 10/614,354 | 07/07/2003 | Thomas J. Sonderman | 2000.100800 | 7900 |
| 23720 | 7590 | 03/31/2006 | | |
| WILLIAMS, MORGAN & AMERSON 10333 RICHMOND, SUITE 1100 HOUSTON, TX 77042 | | | EXAMINER NGUYEN, KHIEM D | |
| | | | ART UNIT | PAPER NUMBER |
| | | | 2823 | |

DATE MAILED: 03/31/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.

10/614,354

Applicant(s)

SONDERMAN ET AL.

Examiner

Khiem D. Nguyen

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-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 17 January 2006.
- 2a) ☒ This action is **FINAL**. 2b) ☐ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1,3,6-9,11-15,21 and 22 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1,3,6-9,11-15,21 and 22 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☒ The drawing(s) filed on 07 July 2003 is/are: a) ☒ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. _____.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- 1) ☐ Notice of References Cited (PTO-892)
- 2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) ☐ Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date _____
- 4) ☐ Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____
- 5) ☐ Notice of Informal Patent Application (PTO-152)
- 6) ☐ Other: _____

DETAILED ACTION***Claim Rejections - 35 USC § 102***

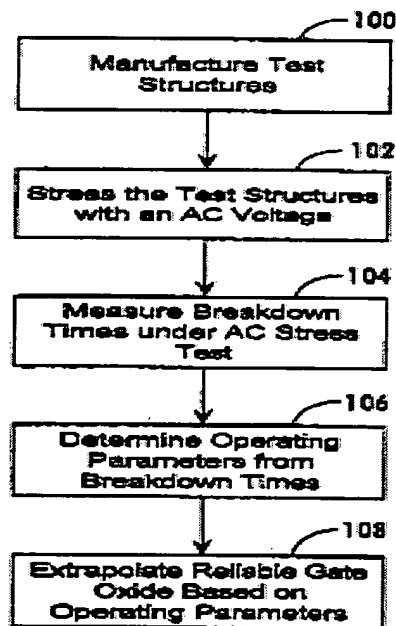
The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1, 3, 6-9, 11-15, and 21-22 are rejected under 35 U.S.C. 102(b) as being anticipated by Fang et al. (U.S. Patent 6,133,746).

In re claims 1 and 9, Fang discloses a method, comprising: performing at least one electrical test **102** on at least one flash memory device (col. 1, lines 35-48) to determine a duration of a programming cycle **104** performed on the flash memory device;

**FIG. 1**

determining at least one parameter **106** of at least one process operation to be performed to form at least one gate insulation layer **108** on a subsequently formed flash memory device based upon the determined duration of the programming cycle (col. 3, line 66 to col. 4, line 35 and FIG. 1); and

performing the at least one process operation comprised of the determined at least one parameter to form at least one gate insulation layer **108** on the subsequently formed flash memory device (col. 4, line 36 to col. 5, line 21 and FIG. 1).

In re claims 3 and 11, **Fang** discloses that performing the at least one electrical test on the at least one flash device further comprises performing the at least one electrical test on the at least one flash memory device to determine at least one of a breakdown voltage, a threshold voltage, a state charge, an interface charge, a trapped charge, a surface charge, and an erase cycle time (col. 3, line 66 to col. 4, line 35).

In re claims 6 and 13, the technique of performing the at least one process operation comprised at least one of a deposition process and a thermal growth process to form the at least one gate insulation layer on the subsequently formed semiconductor device using a new thickness recipe upon obtaining a new parameter is well-known to one of ordinary skill in the art at the time of the invention was made.

In re claims 7 and 14, **Fang** discloses that at least one parameter is comprised of at least one of a temperature, a pressure, a duration, a process gas flow rate, a process gas composition, a liquid flow rate, a liquid composition, and a power level setting (col. 3, line 66 to col. 4, line 35).

In re claims 8 and 15, **Fang** discloses that the gate insulation layer is comprised of at least one of silicon dioxide and silicon nitride (col. 5, lines 10-21).

In re claim 12, **Fang** discloses that the semiconductor device is comprised of a memory device that is comprised of a gate insulation layer, a floating gate layer positioned above the gate insulation layer, an intermediate insulation layer positioned above the floating gate layer, and a control gate layer positioned above the intermediate insulation layer (col. 1, lines 11-21).

In re claims 21 and 22, **Fang** discloses a method, comprising: performing at least one electrical test **102** on at least one memory device (col. 1, lines 35-48) to determine a duration of a programming cycle **104** performed on the memory devices;

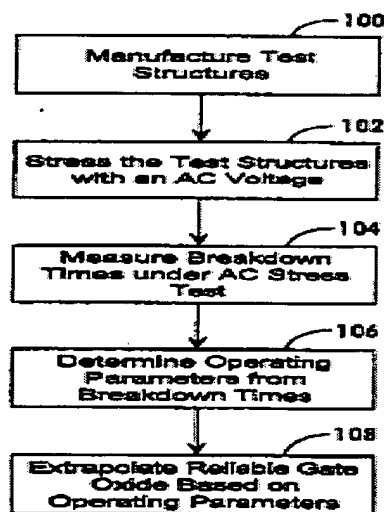


FIG. 1

determining at least one parameter **106** of at least one process operation to be performed to form at least one gate insulation layer **108** on a subsequently formed

memory device based upon the determined duration of the programming cycle (col. 3, line 66 to col. 4, line 35 and FIG. 1); and

performing the at least one process operation comprised of the determined at least one parameter to form **108** at least one gate insulation layer on the subsequently formed memory device (col. 4, line 35 to col. 5, line 21).

Response to Applicants' Amendment and Arguments

Applicant's arguments filed January 17th, 2006 have been fully considered but they are not persuasive.

Applicants contend that there reference Fang et al. (U.S. Patent 6,133,746) herein known as Fang does not teach or suggest the disclosure of "determining at least one parameter of at least one process operation to be performed to form at least one gate insulation layer on a subsequently formed flash memory device based upon said determined duration of said programming cycle".

In response to Applicants' contention that Fang does not teach or suggest the disclosure of "determining at least one parameter of at least one process operation to be performed to form at least one gate insulation layer on a subsequently formed flash memory device based upon said determined duration of said programming cycle", Examiner respectfully disagrees. Applicants are directed to (col. 1, lines 21-34) where Fang disclosed that selected cells are programmed to a higher threshold voltage by applying a high voltage, such as 18V-23V, for a period of time, such as about 200 μ s, to the word lines of the selected cells. Thus, Fang inherently disclosed performing at least one electrical test (threshold voltage) on at least one flash memory device (EEPROMs)

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(col. 1, lines 11-21) to determine a duration of a programming cycle performed on the flash memory device; and determining at least one parameter (duration) of at least one process operation to be performed to form at least one reliable gate insulation layer on a subsequently formed flash memory device based upon the determined duration of the programming cycle (col. 4, line 36 to col. 5, line 21).

For this reason, Examiner holds the rejection proper.

Conclusion

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Khiem D. Nguyen whose telephone number is (571) 272-1865. The examiner can normally be reached on Monday-Friday (8:30 AM - 5:30 PM).

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew S. Smith can be reached on (571) 272-1907. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

K.N.
March 24th, 2006



**W. DAVID COLEMAN
PRIMARY EXAMINER**